



Rika Taslim &lt;rikataslim@gmail.com&gt;

## Invitation to review for Chinese Journal of Chemical Engineering

1 message

**Chinese Journal of Chemical Engineering** <em@editorialmanager.com>

Sun, Nov 7, 2021 at 5:00 PM

Reply-To: Chinese Journal of Chemical Engineering &lt;cjche@elsevier.com&gt;

To: Rika Taslim &lt;rikataslim@gmail.com&gt;

Manuscript Number: CJCHE-D-21-01574

Self-deposition for N-doping mesoporous carbon nanosheet with supercapacitor application

Juan Du; Aibing Chen; Senlin Hou; Xueqing Gao

Dear Taslim,

I would like to invite you to review the above referenced manuscript submitted by Dr. Aibing Chen, as I believe it falls within your expertise and interest. The abstract for this manuscript is included below.

You should treat this invitation, the manuscript and your review as confidential. You must not share your review or information about the review process with anyone without the agreement of the editors and authors involved, even after publication. This also applies to other reviewers' "comments to author" which are shared with you on decision (and vice versa).

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Since timely reviews are of utmost importance to authors, I would appreciate receiving your review within 14 days of accepting this invitation.

I hope you will be able to review this manuscript.

Thank you in advance for your contribution and time.

As a reviewer you are entitled to complimentary access to references, abstracts, and full-text articles on ScienceDirect and Scopus for 30 days. Full details on how to claim your access via Reviewer Hub ([reviewerhub.elsevier.com](http://reviewerhub.elsevier.com)) will be provided upon your acceptance of this invitation to review.

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Kind regards,

CJCHE Editor  
Subject editor (EIC)  
Chinese Journal of Chemical Engineering

Abstract:

Porous carbon sheets have wide application prospects in many fields, especially in energy storage of supercapacitor due to the features combining both 2D structure and porous architectures. Herein, a self-deposition approach is proposed to obtain N-doped mesoporous carbon nanosheets (N-MCNs), using 3-aminophenol (3-AF) as precursor and Mg(OH)<sub>2</sub>

sheet as hard template. This process realizes the direct carbon formation using 3-AF monomer as carbon precursor under the catalysis of hard template avoiding the polymerization and utilization of solvent. The mass ratio of 3-AF to Mg(OH)<sub>2</sub> plays an important role in determining the pore structures and the resulting capacitance behavior. The results show that N-MCNs with a mass ratio of 3-AF and Mg(OH)<sub>2</sub> of 1:1 have good electrochemical behavior for supercapacitors. This N-MCNs based electrode exhibits a high capacitance of 240 F g<sup>-1</sup> at 1 A g<sup>-1</sup>, good rate performance (75.4% retention ratio at 20 A g<sup>-1</sup>), and high cycling stability with 98.3% initial capacitance retained after 10000 cycles. Symmetric supercapacitors on N-MCNs achieve energy density of 18.2 Wh kg<sup>-1</sup> and power density of 0.4 kW kg<sup>-1</sup> operated within a wide potential range of 0-1.6 V in 1.0 M Na<sub>2</sub>SO<sub>4</sub> solution, exhibiting its potential for electrode materials with high performance.

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Rika Taslim &lt;rikataslim@gmail.com&gt;

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## Thank you for reviewing for Chinese Journal of Chemical Engineering

1 message

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**Chinese Journal of Chemical Engineering** <em@editorialmanager.com>

Thu, Dec 2, 2021 at 9:38 PM

Reply-To: Chinese Journal of Chemical Engineering &lt;cjche@elsevier.com&gt;

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Juan Du; Aibing Chen; Senlin Hou; Xueqing Gao

Dear Dr Taslim,

Thank you for reviewing the above referenced manuscript. I greatly appreciate your contribution and time, which not only assisted me in reaching my decision, but also enables the author(s) to disseminate their work at the highest possible quality. Without the dedication of reviewers like you, it would be impossible to manage an efficient peer review process and maintain the high standards necessary for a successful journal.

I hope that you will consider Chinese Journal of Chemical Engineering as a potential journal for your own submissions in the future.

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Kind regards,

CJCHE Editor  
Subject editor (EIC)  
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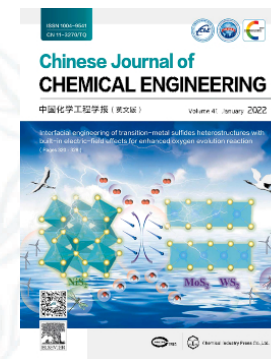
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Chinese Journal of Chemical Engineering

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